

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-586003	Application No. 10/802,991
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Lawrence D. Wong	
		Filing Date March 16, 2004	Group Art Unit 1792

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
/MLP/	AA	4,848,141	07/1989	Oliver et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
	AH						Yes	No
	AI							
	AJ							

"Structural Change in Porous Silica Thin Film after Plasma Treatment"

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
/MLP/	AK	"The Effects of Plasma Treatment for Low Dielectric Constant Hydrogen Silsesquioxane Document (HSQ)"
/MLP/	AL	P.T. Liu et al., Thin Solid Films 332 (1998) 345-350. (no month)
/MLP/	AM	E. Kondoh, Electrochemical and Solid-State Letters, 1 (5) 224-226 (1998) (no month)
/MLP/	AN	Gidley et al., Applied Physics Letters, 76 (2000) p. 1282
/MLP/	AO	Loboda et al., Using trimethylsilane to improve safety, throughput and versatility in PECVD processes, Proceedings of the Symposium on Silicon Nitride and Silicon Dioxide Thin Insulating Films, 1997, p. 445-453 (no month) vol. 97-10, Electrochemical Proceedings, D. 443-453
/MLP/	AP	Loboda et al., Deposition of low-k dielectric films using trimethylsilane, Proceedings of the Symposium on Electrochemical Processing in ULSI Fabrication and Interconnect and Contact Metallization: Materials, Processes, and Reliability, 1998, p. 145-152. no other info on sheets
/MLP/	AQ	Sugahara et al., Low Dielectric Constant Carbon Containing SiO ₂ Films Deposited by PECVD Techniques Using a Novel CVD Precursor, International dielectrics for ULSI multilevel interconnection conference, 1997, p. 19-25. February
/MLP/	AK	Kanaya K. and Okayama S., Journal of Physics D. Applied Physics. 5-43 (1972).
		Penetration and Energy-loss Theory of Electrons in Solid Targets" vol. 5, p. 43-58 (no month)

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found,
match

Examiner Signature /Marianne L. Padgett/	Date Considered 10/16/2007
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Notice of References Cited

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Application/Control No.
10559-586003
March 16, 2004Applicant(s)/Patent Under
Reexamination
10/802,991Examiner
ML PadgettArt Unit
17922 of 3
Page ~~1 of 1~~**U.S. PATENT DOCUMENTS**

*		Document Number	Date	Name	Classification
		Country Code-Number-Kind Code	MM-YYYY		
/MLP/	A	US-6,340,628 B1	01-2002	Van Cleemput et al.	438/586
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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*		Document Number	Date	Country	Name	Classification
		Country Code-Number-Kind Code	MM-YYYY			
	N					
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		Examiner ML Padgett	Art Unit 1792	3 of 3 Page 1 of 1

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	Q					
	R					
	S					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
/MLP/	U	abstract from dialog(R) file of Hara et al., "Mechanism of mechanical and chemical polishing in low dielectric constant plasma-enhanced chemical vapor deposition SiOC layer from hexamethyldisiloxane", Aug. 2001, Electrochem. and Solid-State Lett., vol. 4, no. 8, P. G65-67. no copy of article found in parent			
/MLP/	V	Music et al., "Synthesis and mechanical properties of boron suboxide thin films", Apr 2002, J. Vac. Sci. Technol. A 20(2), p.335-337.			
	W				
	X				

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		Filing Date March 16, 2004	Group Art Unit: 1762 1792

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/MLP/	AA	US 2005/0194619	09/2005	Edelstein, et al.			
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	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
/MLP/	AQ	Office Action Mailed July 16, 2007 for Application Number 10/802,331 filed March 16, 2004 (Attorney Docket Number 10559-586002) not a published document
	AR	
	AS	
	AT	

Examiner Signature /Marianne L. Padgett/	Date Considered 10/16/2007
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